

PATENT ABSTRACTS OF JAPAN(11)Publication number : **2004-307906**(43)Date of publication of application : **04.11.2004**

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C23C 14/34(21)Application number : **2003-100782**(71)Applicant : **KOBELCO KAKEN:KK**(22)Date of filing : **03.04.2003**(72)Inventor : **MATSUMURA HITOMI
YONEDA YOICHIRO****(54) SPUTTERING TARGET, AND METHOD FOR MANUFACTURING THE SAME****(57)Abstract:**

PROBLEM TO BE SOLVED: To provide a very large sputtering target obtained by butt-welding metal plates of the same quality in which the grain size and the dispersed state of metal crystals and intermetallic compounds are substantially equal between a welded zone and a non-welded zone.

SOLUTION: The mean grain size of intermetallic compounds of a welded zone is 60-130% of the mean grain size of intermetallic compounds of a non-welded zone.

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